Electronic Supplementary Material (ESI) for Physical Chemistry Chemical Physics.

Chemical induced porosity on $BiVO_4$ films produced by double magnetron sputtering to enhance the photo-electrochemical response

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Supporting Information

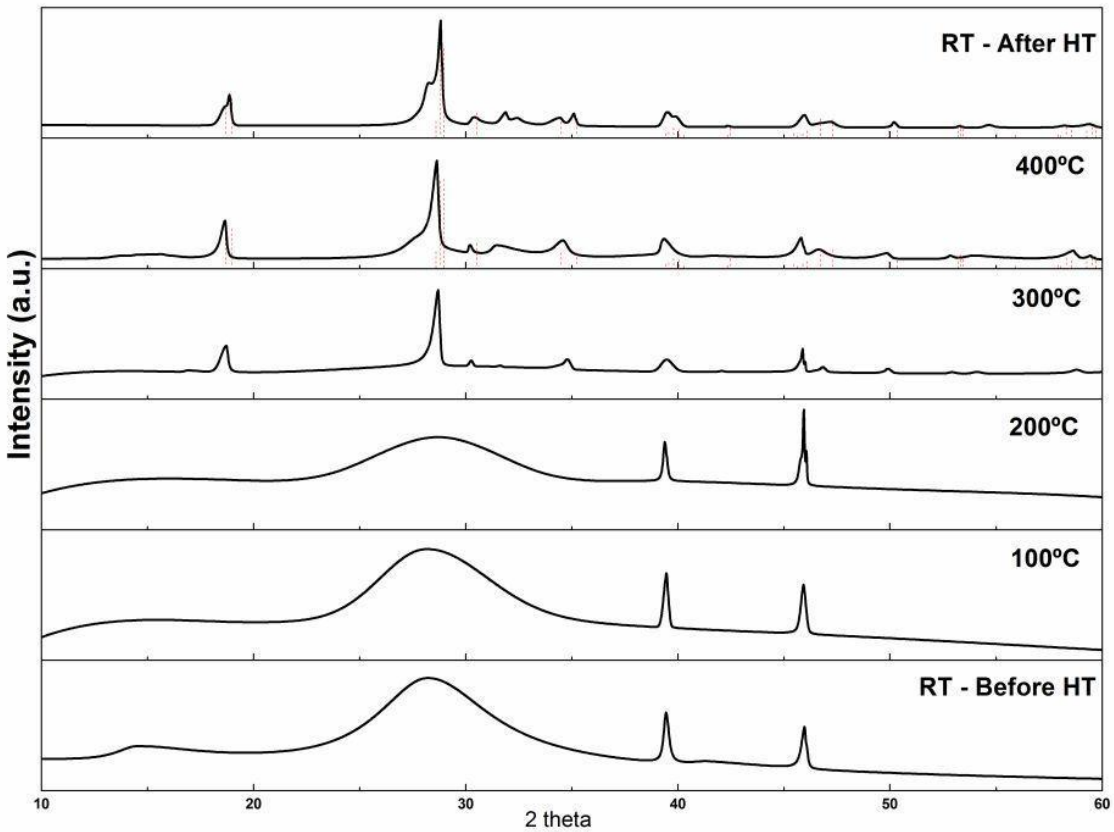

Fig S1: XRD profile of $BiVO_4$ film made by DMS under in-situ temperature increase analysis. RT stay for the XRD patterns obtained at room temperature, before and after the heat treatment (HT).

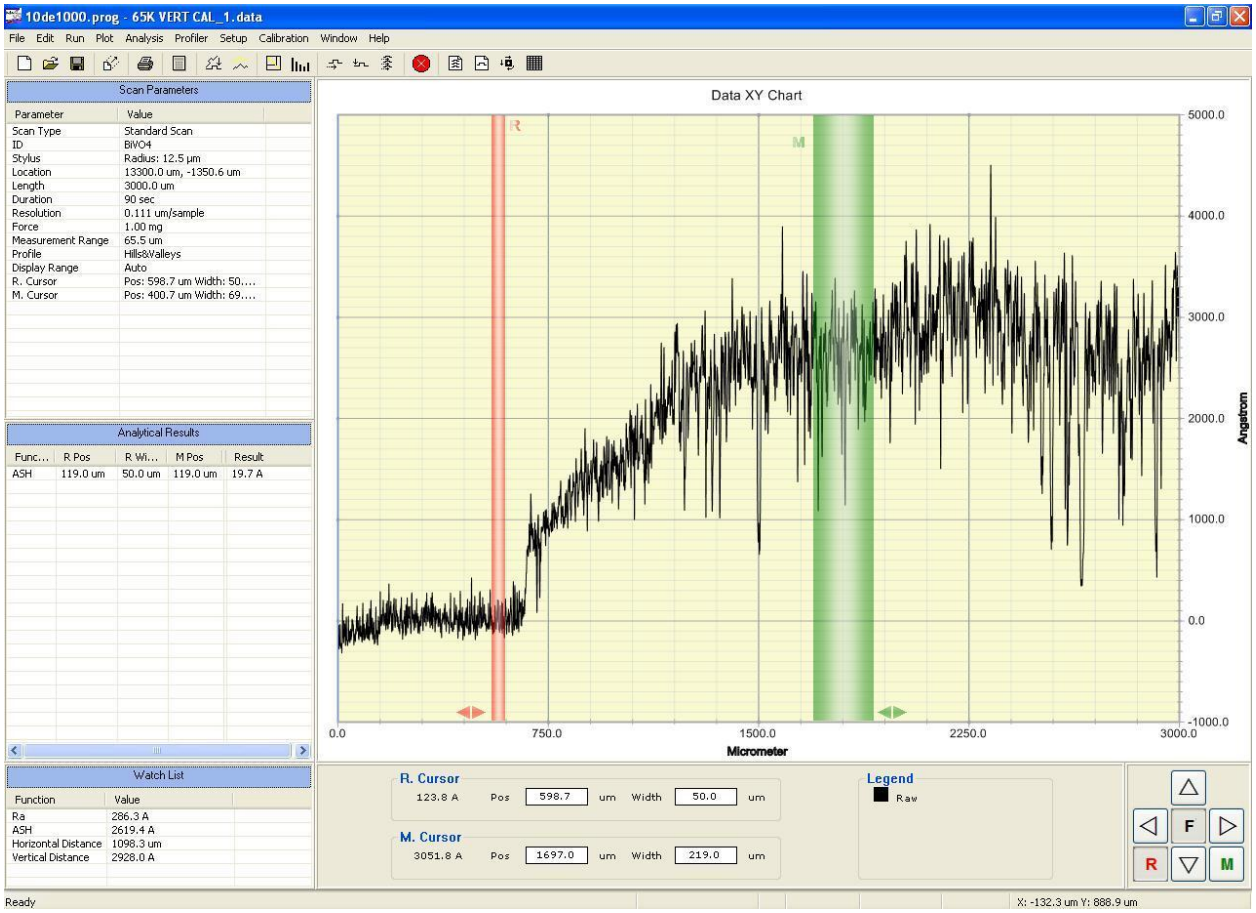

Fig S2: Profilometric measurement of the $BiVO_4$ film after the KOH treatment.